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4. METHODS TO ASSESS WIPER QUALITY5. THE IMPORTANCE OF AUTOMATION; 6. APPLICATIONS; 7. CURRENT TRENDS IN WIPER TECHNOLOGY; 8. FUTURE DEVELOPMENTS IN CLEAN ROOM WIPERS; REFERENCES; Chapter 4 - Impact of Microbial Surface Contamination and Effective Environment Monitoring System in Pharmaceutical Manufacturing; 1. INTRODUCTION; 2. IMPACT OF MICROORGANISMS IN THE ENVIRONMENT; 3. SANITIZATION; 4. ENVIRONMENTAL MONITORING; 5. ENVIRONMENTAL CONTAMINATION CONTROL; 6. FUTURE DEVELOPMENTAL REQUIREMENTS; REFERENCES
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Sommario/riassunto

In this series, Rajiv Kohli and Kash Mittal have brought together the work of experts from different industry sectors and backgrounds to provide a state-of-the-art survey and best-practice guidance for scientists and engineers engaged in surface cleaning or dealing with the consequences of surface contamination. This volume complements Volumes 3 and 4 of this series, which focused largely on particulate contaminants. The expert contributions in this volume cover methods for removal of non-particulate contaminants, such as metallic and non-metallic thin films, hydrocarbons, toxic and